

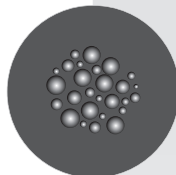
CINOS CLEANING TECHNOLOGY

SUPER SONIC CLEAN

SSC™



Pulsation



Various Size



Sensitive

CINOS

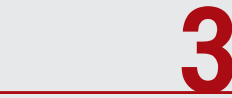
WE MAKE GLOBAL STANDARD



1
Substrate Contaminated with Particles of Various Sizes.



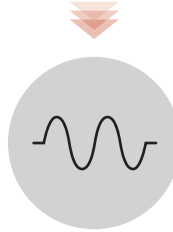
2
Removal of Small, Medium, Large Size Particles by Using Various Frequencies.



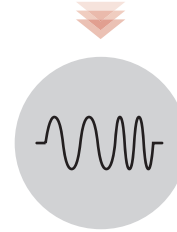
3
Substrate with Particles Removed.

Benefits

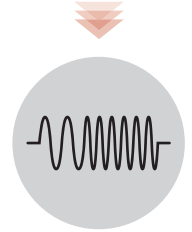
3 Frequency Cleaning



α Frequency
Large Size Particle Remove



β Frequency
Medium Size Particle Remove

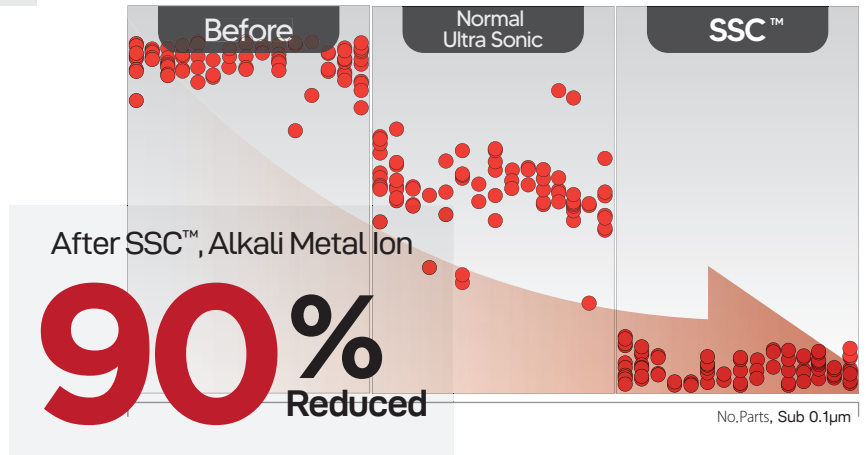


γ Frequency
Ultra Small Size Particle Remove

Excellent Cleaning Technology for Removing Ultra Small ~ Large Size Particles, SSC™

Mechanism

Techniques for cleaning parts used in general semiconductor processes include immersion, spraying, and dry ultrasonication, but they are not suitable for dealing with particles of various sizes. Ultra-small size particles are specifically difficult to remove due to substrate zeta potential induced by the size by the pre-existing method. SSC™ can oscillate various frequencies to remove particles of various sizes for each frequency. In the case of high frequency, SSC™ is a technology suitable for sensitive cleaning to remove ultra-small size particles.



Application

Best Solution

For Alkali Metal Ion

Cleaning

- ShowerHead
- ShowerHead Base
- Electrode Inner

ShowerHead Series



ShowerHead Base



Electrode Inner

